



GAU 1765

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4/27/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Anne E. Miller et al.

Application No.: 09/461,158

Filed: December 14, 1999

For: HIGH pH SLURRY FOR CHEMICAL
MECHANICAL POLISHING OF
COPPERCommissioner for Patents
Washington, D.C. 20231

Group Art Unit: 1765

Examiner: Charlotte A. Brown

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Signature

Date

RESPONSE TO RESTRICTION REQUIREMENT

Dear Sir:

In response to the Office Action mailed January 17, 2001, Applicants respectfully
elect claims 1-14 (Group I) without traverse. Please cancel the non-elected claims 15-27.

Respectfully Submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN, LLP

Dated: April 16, 2001
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